39. The substrate of claim 36 wherein the antireflective composition further comprises a melamine crosslinker component.

40. The substrate of claim 36 wherein the antireflective composition comprises a thermal acid generator.

41. The substrate of claim 36 wherein the antireflective composition comprises an anthracene material.

42. The substrate of claim 36 wherein the substrate is a microelectronic wafer.

43. A coated substrate comprising:

a substrate having thereon:

a coating layer of an antireflective composition, the antireflective composition comprising a crosslinker and an anthracene material; and

a coating layer of a photoresist composition over the antireflective layer.

44. The substrate of claim 43 wherein the antireflective composition layer is crosslinked.

45. The substrate of claim 43 wherein the antireflective composition comprises a thermal acid generator.

46. The substrate of claim 43 wherein the substrate is a microelectronic wafer.

47. A method for forming a relief image on a substrate comprising:

applying on the substrate a layer of an antihalation composition comprising a benzoguanamine crosslinker;

applying over the antihalation composition layer a photoresist composition.

48. The method of claim 47 wherein the antihalation composition layer is crosslinked prior to applying the photoresist composition.

49. The method of claim 47 wherein the antireflective composition comprises a benzoguanamine resin.

50. The method of claim 47 wherein the antireflective composition further comprises a melamine crosslinker component.

51. The method of claim 47 wherein the antireflective composition comprises a thermal acid generator.

52. The method of claim 47 wherein the antireflective composition comprises an anthracene material.

53. The method of claim 47 wherein the substrate is a microelectronic wafer.

54. A method for forming a relief image on a substrate comprising:

applying on the substrate a layer of an antihalation composition comprising an anthracene material;

applying over the antihalation composition layer a photoresist composition.